

PENDING CLAIMS

The following is a complete list of claims currently pending in the application. No claims have been added, amended, or deleted in the present correspondence.

1. (Original) A method of forming an active device, the method comprising:
performing a first patterning operation on a first plurality of layers, the first patterning operation defining a first feature of the active device; and
performing a second patterning operation on at least one patterned layer of the first plurality of layers, the second patterning operation defining a second feature of the active device, wherein the first and second patterning operations are performed substantially back-to-back.
2. (Original) The method of Claim 1, wherein the first patterning operation includes:
etching the first plurality of layers into a first plurality of strips oriented in a first direction.
3. (Original) The method of Claim 2, wherein the second patterning operation includes:
etching at least one strip of the first plurality of strips in a second direction, the second direction being different than the first direction, to create a pillar.
4. (Original) The method of Claim 3, wherein at least one strip of the first plurality of strips comprises a first terminal of the active device.
5. (Original) The method of Claim 4, wherein the pillar comprises another portion of the active device.
6. (Original) The method of Claim 4, further including:

depositing a first dielectric after both first and second patterning operations; and planarizing the first dielectric to expose a surface of the active device.

7. (Original) The method of Claim 6, further including performing a cleaning step after planarizing.

8. (Original) The method of Claim 6, further including:
depositing a second plurality of layers on the surface of the active device and the first dielectric; and
etching the second plurality of layers into a second plurality of strips oriented in the second direction.

9. (Original) The method of Claim 8, wherein said second plurality of strips is not self-aligned to the pillar.

10. (Original) The method of Claim 8, wherein at least one strip of the second plurality of strips comprises a second terminal of the active device.

11. (Original) The method of Claim 1, wherein the first plurality of layers includes an antifuse layer fully etched through by the first patterning operation, but not fully etched through by the second patterning operation.

12. (Original) The method of Claim 1, wherein the first plurality of layers includes an antifuse layer fully etched through by both the first and second patterning operations.

13-67. (Withdrawn)